

AMENDMENTS TO THE CLAIMS

1-53. (Cancelled)

54. (New): A liquid crystal display (LCD) device comprising:

- a first substrate and a second substrate;
- an inorganic insulating layer made of one of silicon oxide and silicon nitride on a first side of the first substrate;
- a light emitting structure including an organic light emitting layer on the inorganic insulating layer;
- a protective layer on the light emitting structure to protect the light emitting structure;
- a thin film transistor (TFT) array structure including thin film transistors and pixel electrodes on a second side of the first substrate, wherein the first side is opposite to the second side;
- a common electrode on a surface of the second substrate; and
- a liquid crystal layer between the first substrate and the second substrate, whereby the light emitting structure shares the first substrate with the TFT array structure.

55. (New): The LCD of claim 54, wherein the light emitting structure is a light emitting diode.

56. (New): The LCD of claim 54, wherein the light emitting structure comprises:

- a first electrode disposed on the inorganic insulating layer;
- the organic light emitting layer on the first electrode; and
- a second electrode on the organic light emitting layer.

57. (New): The LCD of claim 56, wherein the organic light emitting layer comprises:

- a hole transport layer;
- an organic light emitting layer; and
- an electron transport layer.

58. (New): The LCD of claim 54, wherein the organic light emitting layer comprises any one of Alq3 (tris-8-hydroxyquinolinato aluminum), BeBq (bis-benzo-quinolinato-berellium), PPV

(polyphenylenevinylene) or polyalkylthiophene.

59. (New): The LCD of claim 56, wherein the first electrode is indium tin oxide.

60. (New): The LCD of claim 54, wherein the first substrate is composed of an organic material.

61. (New): The LCD of claim 60, wherein the first substrate performs an additional function of polarization.

62. (New): The LCD of claim 54, wherein the protective layer includes SiOx or IOx.

63. (New): A method for fabricating a liquid crystal display (LCD) device, comprising:
 depositing a first insulating layer on a first surface of a first substrate;
 after depositing the first insulating layer, sequentially depositing a first electrode on the first insulating layer, an organic film layer on the first electrode and a second electrode on the organic film layer to form a light emitting structure;
 after forming the light emitting structure, depositing a protective layer to protect the light emitting structure;
 forming a thin film transistor array on a second surface of the first substrate;
 providing a liquid crystal layer on the second surface of the first substrate; and
 attaching the first substrate to a second substrate.

64. (New): The method of claim 63, wherein the light emitting structure is a light emitting diode.

65. (New): The method of claim 63, wherein forming the organic film layer comprises:
 forming a hole transport layer;
 forming an organic light emitting layer; and
 forming an electron transport layer.

66. (New): The method of claim 65, wherein the organic light emitting layer comprises any one of Alq3 (tris-8-hydroxyquinolinato aluminum), BeBq (bis-benzo-quinolinato-berellium), PPV

(polyphenylenevinylene) or polyalkylthiophene.

67. (New): The method of claim 63, wherein the first electrode is indium tin oxide.

68. (New): The method of claim 63, wherein the first substrate is comprised of an organic material.

69. (New): The method of claim 68, wherein the first substrate performs an additional function of polarization.

70. (New): The method of claim 63, wherein the first insulating layer includes either SiOx or SiNx.

71. (New): The method of claim 63, wherein the protective layer includes SiOx or IOx.